

L Number	Hits	Search Text	DB	Time stamp
1	0	(sidewall adj polymer adj deposition) and (patterned adj microelectronic adj layer)	USPAT	2004/07/13 15:54
2	0	(vertically adj etched adj blanket adj target) and incompletely and (plasma adj etch adj method) and (patterned adj layer)	USPAT	2004/07/13 15:56
3	0	(vertically adj etched adj blanket adj target) and incompletely and (plasma adj etch adj method)	USPAT	2004/07/13 15:57
4	0	vertically and incompletely and (plasma adj etch adj method) and spacer and side and wall and residue and pattern and etch and mask	USPAT	2004/07/13 15:59
5	1	("5453156").PN.	USPAT	2004/07/13 15:59
6	1	("6110837").PN.	USPAT	2004/07/13 15:59
7	1	("6391788").PN.	USPAT	2004/07/13 15:59
8	1	((("5453156").PN.) and (pattern or patterned or side or wall or spacer or pair or blanket or target or incompletely or vertically or etch or etched or etching or mask or residue or removing or pasma or mateiral or conductive or conductor or fluoro or polymer or gate or electrode)	USPAT	2004/07/13 16:08
9	1		USPAT	2004/07/13 16:07
10	1		USPAT	2004/07/13 16:08
11	1		USPAT	2004/07/13 16:08
12	1		USPAT	2004/07/13 16:08
13	1	((("6110837").PN.) and (pattern or patterned or side or wall or spacer or pair or blanket or target or incompletely or vertically or etch or etched or etching or mask or residue or removing or pasma or mateiral or conductive or conductor or fluoro or polymer or gate or electrode)	USPAT	2004/07/13 16:19
14	1		USPAT	2004/07/13 16:15
15	1		USPAT	2004/07/13 16:15
16	1		USPAT	2004/07/13 16:16
17	1		USPAT	2004/07/13 16:17
18	1		USPAT	2004/07/13 16:18
19	1		USPAT	2004/07/13 16:18
20	1	((("6391788").PN.) and (pattern or patterned or side or wall or spacer or pair or blanket or target or incompletely or vertically or etch or etched or etching or mask or residue or removing or pasma or mateiral or conductive or conductor or fluoro or polymer or gate or electrode)	USPAT	2004/07/13 16:21
21	1		USPAT	2004/07/13 16:20
22	1		USPAT	2004/07/13 16:20
23	1		USPAT	2004/07/13 16:21
24	1		USPAT	2004/07/13 16:21
25	1		USPAT	2004/07/13 16:21
26	1	"5916821".PN. and (pattern or patterned or side or wall or spacer or pair or blanket or target or incompletely or vertically or etch or etched or etching or mask or residue or removing or pasma or mateiral or conductive or conductor or fluoro or polymer or gate or electrode)	USPAT	2004/07/13 16:23
27	1	"5902133".PN. and (pattern or patterned or side or wall or spacer or pair or blanket or target or incompletely or vertically or etch or etched or etching or mask or residue or removing or pasma or mateiral or conductive or conductor or fluoro or polymer or gate or electrode)	USPAT	2004/07/13 16:25
28	1	"5296410".PN. and (pattern or patterned or side or wall or spacer or pair or blanket or target or incompletely or vertically or etch or etched or etching or mask or residue or removing or pasma or mateiral or conductive or conductor or fluoro or polymer or gate or electrode)	USPAT	2004/07/13 16:27

7/13/04

29	1	((("6110837").PN.) and (pattern or patterned or side or wall or spacer or pair or blanket or target or incompletely or vertically or etch or etched or etching or mask or residue or removing or pasma or mateiral or conductive or conductor or fluoro or polymer or gate or electrode)	USPAT	2004/07/13 16:29
30	892	438/689	USPAT	2004/07/13 16:29
31	632	438/695	USPAT	2004/07/13 16:30
32	531	438/704	USPAT	2004/07/13 16:30
33	1564	438/706	USPAT	2004/07/13 16:30
34	451	438/717	USPAT	2004/07/13 16:30
35	1459	438/723	USPAT	2004/07/13 16:30
36	805	438/724	USPAT	2004/07/13 16:30
37	1031	438/725	USPAT	2004/07/13 16:30
38	705	438/734	USPAT	2004/07/13 16:30
39	417	438/735	USPAT	2004/07/13 16:30
40	959	438/738	USPAT	2004/07/13 16:31
41	655	438/743	USPAT	2004/07/13 16:31
42	377	438/744	USPAT	2004/07/13 16:31
43	1346	438/745	USPAT	2004/07/13 16:31
44	248	438/942	USPAT	2004/07/13 16:31
45	162	438/954	USPAT	2004/07/13 16:31
46	144	438/963	USPAT	2004/07/13 16:31